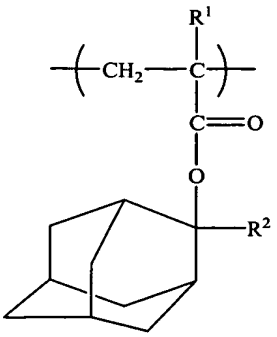
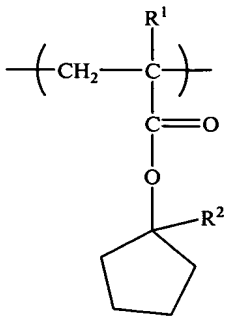
IN THE CLAIMS

1. (Original) A radiation-sensitive resin composition comprising:

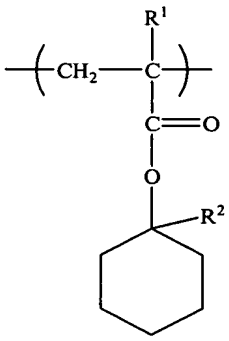
(A) a resin comprising at lest two recurring units of the following formulas (1) - (6),



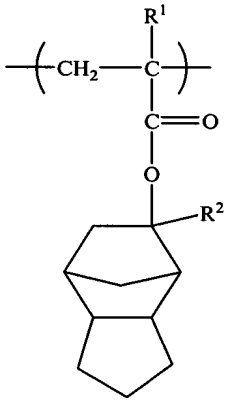
(1)



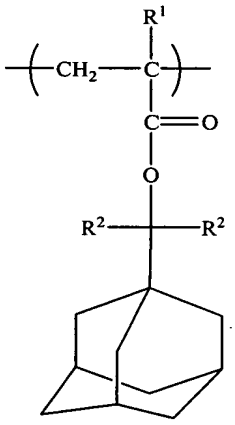
(2)



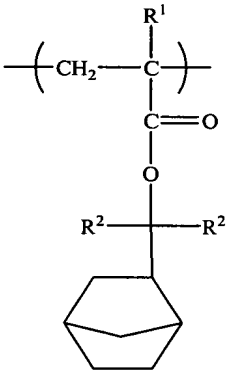
(3)



(4)



(5)

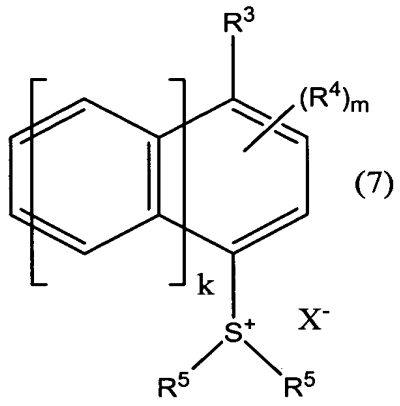


(6)

wherein R^1 represents a hydrogen atom or methyl group and R^2 represents a substituted or unsubstituted alkyl group having 1-4 carbon atoms, two or more R^2 groups that may be present being either the same or different, in the total amount of 5 - 7 mol %, but each in the amount of 1 - 49 mol %, the resin being insoluble or scarcely soluble in alkali, but becoming easily soluble in alkali by the action of an acid, and

(B) a photoacid generator.

2. (Original) The radiation-sensitive resin composition according to Claim 1, wherein the photoacid generator (B) is compound shown by the formula (7),



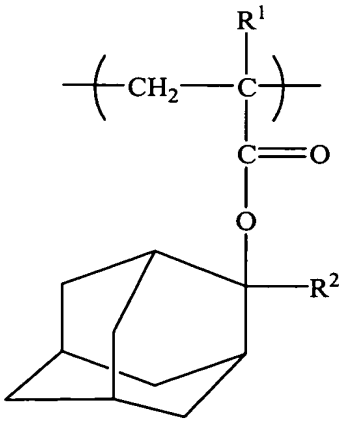
(7)

wherein R^3 represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1 - 10 carbon atoms, linear or branched alkoxyl group having 1 - 10 carbon atoms, or linear or branched alkoxycarbonyl group having 2 - 11 carbon atoms, R^4 represents a linear or branched alkyl group having 1 -10 carbon atoms, R^5 individually represents a linear or branched alkyl group having 1 - 10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two R^5 groups bond to form a substituted or unsubstituted divalent group having 2 - 10 carbon atoms, k is an integer of 0 to 2, X^- represents an anion represented by the formula $R^6C_nF_{2n}SO_3^-$ (wherein R^6 represents a fluorine atom or substituted or unsubstituted monovalent hydrocarbon group and n is an integer of 1 to 10), and m is an integer of 1 to 10.

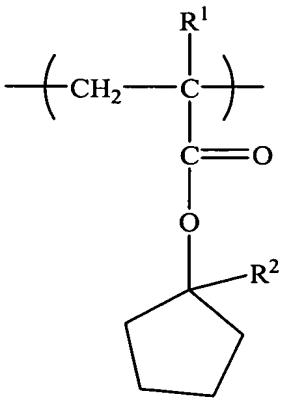
3. (Original) The radiation-sensitive resin composition according to Claim 1, wherein the resin (A) and the photoacid generator (B) are dissolved in a solvent comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.

4. (Previously Presented) A radiation-sensitive resin composition comprising:

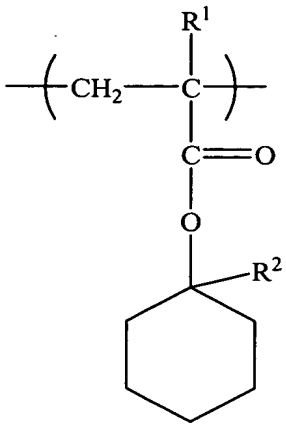
a resin comprising at least two recurring units of the following formulas (1) - (3),



(1)



(2)

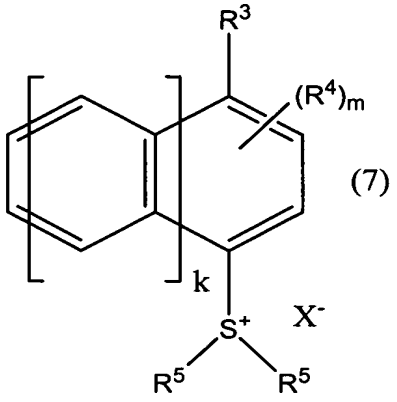


(3)

wherein R^1 represents a hydrogen atom or methyl group and R^2 represents a substituted or unsubstituted alkyl group having 1 - 4 carbon atoms, two or more R^2 groups that may be present being either the same or different, in the total amount of 5 - 70 mol %, but each in the amount of 1 - 49 mol %, the resin being insoluble or scarcely soluble in alkali, but becoming easily soluble in alkali by the action of an acid, and

(B) a photoacid generator.

5. (Previously Presented) The radiation-sensitive resin composition according to Claim 4, wherein the photoacid generator (B) is the compound shown by the formula (7),



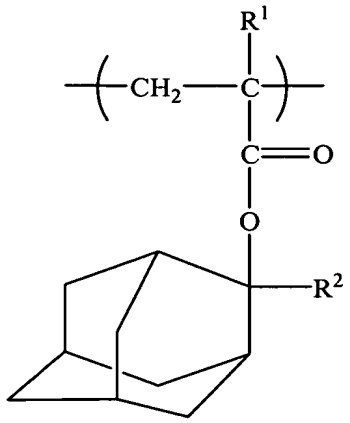
(7)

wherein R^3 represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1 - 10 carbon atoms, linear or branched alkoxyl group having 1 - 10 carbon atoms, or linear or branched alkoxycarbonyl group having 2 -11 carbon atoms, R^4 represents a linear or branched alkyl group having 1 - 10 carbon atoms, R^5 individually represents a linear or branched alkyl group having 1 - 10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two R^5 groups bond to form a substituted or unsubstituted divalent group having 2 - 10 carbon atoms, k is an integer of 0 to 2, X^- represents an anion represented by the formula $R^6C_nF_{2n}SO_3^-$ (wherein R^6 represents a fluorine atom or substituted or unsubstituted monovalent hydrocarbon group and n is an integer of 1 to 10), and m is an integer of 1 to 10.

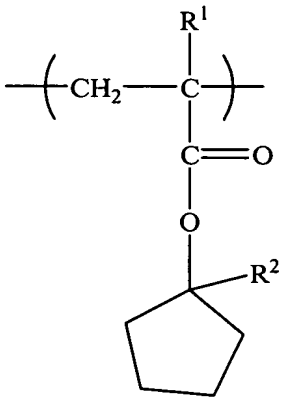
6. (Previously Presented) The radiation-sensitive composition according to Claim 4, wherein the resin (A) and the photoacid generator (B) are dissolved in a solvent comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.

7. (Previously Presented) A radiation-sensitive resin composition comprising,

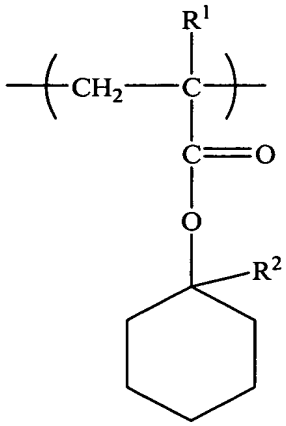
(A) a resin comprising at least one recurring unit of the following formulas (1) - (3),



(1)



(2)

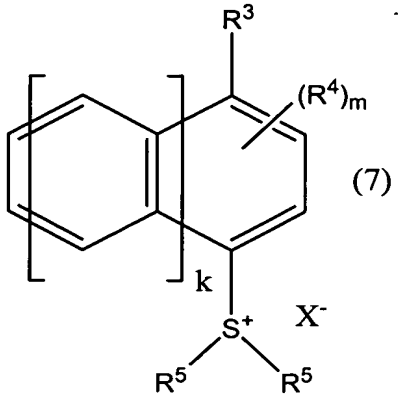


(3)

wherein R^1 represents a hydrogen atom or methyl group and R^2 is a methyl group, and at least one recurring unit of the above formulas (1) - (3), wherein R^1 represents a hydrogen atom or methyl group and R^2 represents a substituted or unsubstituted alkyl group having 1 - 4 carbon atoms, excluding a methyl group, two or more R^2 groups that may be present being either the same or different, in the total amount of 5 - 70 mol %, but each in the amount of 1 - 49 mol %, the resin being insoluble or scarcely soluble in alkali, but becoming easily soluble in alkali by the action of an acid, and

(B) a photoacid generator.

8. (Previously Presented) The radiation-sensitive resin composition according to Claim 7, wherein the photoacid generator (B) is the compound shown by the formula (7),



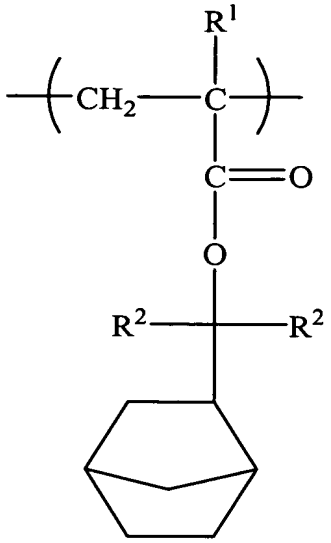
(7)

wherein R^3 represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1 - 10 carbon atoms, linear or branched alkoxyl group having 1 - 10 carbon atoms, or linear or branched alkoxycarbonyl group having 2 - 11 carbon atoms, R^4 represents a linear or branched alkyl group having 1 - 10 carbon atoms, R^5 individually represents a linear or branched alkyl group having 1 -10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two R^5 groups bond to form a substituted or unsubstituted divalent group having 2 - 10 carbon atoms, k is an integer of 0 to 2, X^- represents an anion represented by the formula $R^6C_nF_{2n}SO_3^-$ (wherein R^6 represents a fluorine atom or substituted or unsubstituted monovalent hydrocarbon group and n is an integer of 1 to 10), and m is an integer of 1 to 10.

9. (Previously Presented) The radiation-sensitive resin composition according to Claim 7, wherein the resin (A) and the photoacid generator (B) are dissolved in a solvent comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.

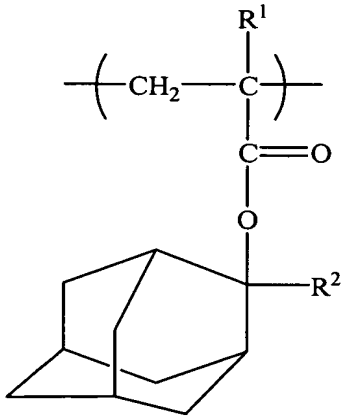
10. (Previously Presented) A radiation-sensitive resin composition comprising,

(A) a resin comprising at least one recurring unit of the following formula (6),

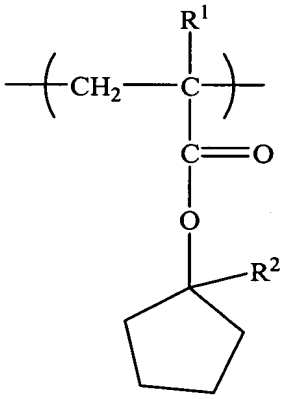


(6)

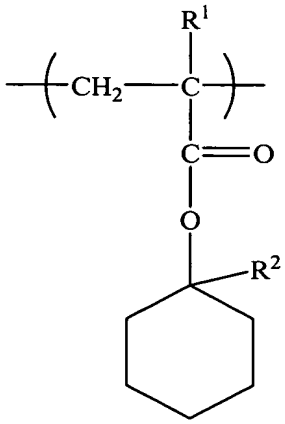
wherein R^2 is a methyl group, and at least one recurring unit selected from the group consisting of the recurring units of the formulas (1) - (3),



(1)



(2)

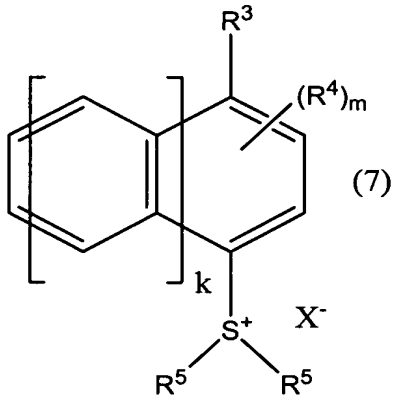


(3)

wherein R^1 represents a hydrogen atom or methyl group and R^2 is a methyl group, in the total amount of 5 - 70 mol %, but each in the amount of 1 - 49 mol %, the resin being insoluble or scarcely soluble in alkali, but becoming easily soluble in alkali by the action of an acid, and

(B) a photoacid generator.

11. (Previously Presented) The radiation-sensitive resin composition according to Claim 10, wherein the photoacid generator (B) is the compound shown by the formula (7),



(7)

wherein R^3 represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1 - 10 carbon atoms, linear or branched alkoxyl group having 1 - 10 carbon atoms, or linear or branched alkoxycarbonyl group having 2 - 11 carbon atoms, R^4 represents a linear or branched alkyl group having 1 - 10 carbon atoms, R^5 individually represents a linear or branched alkyl group having 1 - 10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two R^5 groups bond to form a substituted or unsubstituted divalent group having 2 - 10 carbon atoms, k is an integer of 0 to 2, X^- represents an anion represented by the formula $R^6C_nF_{2n}SO_3^-$ (wherein R^6 represents a fluroine atom or substituted or unsubstituted monovalent hydrocarbon group and n is an integer of 1 to 10), and m is an integer of 1 to 10.

12. (Previously Presented) The radiation-sensitive resin composition according to Claim 10, wherein the resin (A) and the photoacid generator (B) are dissolved in a solvent comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.